

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1.(original): A method for making a transparent conductive film comprising introducing an organozinc compound, a dilution gas, and an oxidizing agent into a deposition chamber to form a transparent conductive film containing zinc oxide as a main component on a substrate disposed in the deposition chamber, wherein the dilution gas is hydrogen.

2.(original): The method for making the transparent conductive film according to Claim 1, wherein the organozinc compound is diethylzinc.

3.(original): The method for making the transparent conductive film according to Claim 1, wherein the oxidizing agent is water.

4.(original): The method for making the transparent conductive film according to Claim 1, wherein a Group III element-containing compound is introduced into the deposition chamber so that the transparent conductive film containing zinc oxide as the main component doped with a small amount of the Group III element is formed on the substrate.

5.(original): The method for making the transparent conductive film according to Claim 4, wherein the Group III element-containing compound is at least one of diborane ( $B_2H_6$ ) and trimethylaluminum ( $(CH_3)_3Al$ ).

6.(currently amended): A method for making a tandem thin-film photoelectric converter comprising a transparent electrode layer, at least one amorphous silicon photoelectric conversion unit, at least one crystalline silicon photoelectric conversion unit, and a back electrode layer stacked in that order on a transparent insulating substrate, the method comprising a step of forming the back electrode layer by the method for making the transparent conductive film according to ~~any one of Claims~~ Claim 1 ~~to 5~~, the transparent insulating substrate being used as the substrate.

7.(currently amended): A method for making a tandem thin-film photoelectric converter comprising a transparent electrode layer, at least one amorphous silicon photoelectric conversion unit, at least one crystalline silicon photoelectric conversion unit, and a back electrode layer stacked in that order on a transparent insulating substrate, the method comprising a step of forming the transparent electrode layer by the method for making the transparent conductive film according to ~~any one of Claims~~ Claim 1 ~~to 5~~, the transparent insulating substrate being used as the substrate.